Influence of Copper Content on Structural and Optical Properties of $Cu2_{(x)}Zn_{(1-x)}S$ Thin Films

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Abstract: $Cu_{(x)}Zn_{(1-x)}Salloy$ was synthesized by reacting high purity elements Cu, Zn, and Swith ratios of Cu = (0.0), (0.25), (0.50), (0.75) and (1.0) in an evacuated quartz ampoule. $Cu_{2(x)}Zn_{(1-x)}S$ thin films have been prepared by vacuum thermal evaporation method from the $Cu_{2(x)}Zn_{(1-x)}Salloy$. The thin films were deposited onto glass substrates undervacuum pressureof 10^{-5} torrwith thickness of 500 nm. The analysis of structural and optical properties of the $Cu_{2(x)}Zn_{(1-x)}S$ thin filmswere carried out by X-ray diffraction (XRD) and UV-Vis Spectrophotometer. The X-Ray diffraction method was utilized to test the $Cu_{2(x)}Zn_{(1-x)}S$ film. It was found that the filmshad a polycrystalline structure with cubic phase and that the average crystal size varied from $(253) A^0$ to $(348) A^0$. The study of the optical properties were carried outwithin a range of wavelength between (200nm) and (1100nm). The average transmission of the films was about (70-90)%. It was decreasing with the increasing of copper concentration (x). The value of absorbancewas very dependent on copper concentration in thin films as the absorbance was proportional with the increase in copper concentrate. The absorption coefficient (α) and optical energy gapwere measured for direct electronic transitions. And the film energy band gap was in the range of (3.10-2.08)eV, depending on the material of the thin films. The refractive index and dielectric constant, at first, increased with the increase of wavelengthand reachedthe largest possible value and then they decreased with the increase of wavelength. The refractive index varied between (1.2) and(2.6).

Keywords: Structural and Optical Properties, Cu2_(x)Zn_(1-x)S thin films

1. Introduction

Copper Zinc Sulfides Cu2(x)Zn(1-x)S have an intermediate feature between Cu₂S and ZnS. The increasing of the Copper(Cu) to a greater degree changes the previous Copper Sulfides compound, Zinc $(Cu2_{(x)}Zn_{(1-x)}S),$ intoCopper Sulfide (Cu₂S) which is used as a buffer window layer material in hetrojunction photovoltaic and photoconductive applications. The $Cu2_{(x)}Zn_{(1-x)}S$ thin films band structure has a larger energy band gap than Cu₂S. This makes the thin film much more appealing for the investigation of solar cells, filters and detecters.[1,2].

The $Cu2_{(x)}Zn_{(1-x)}S$ ternary compound is, furthermore, a possible valuable window material for the creation of a p-n junction without a lattice mismatch in the devices[3].

 $Cu2_{(x)}Zn_{(1-x)}$ Sthin films have been fabricated by several methodes such as: RF-sputtering [4], chemical vapor deposition (CVD) [5],chemical bath deposition (CBD) [6], thermal vacuum evaporation [7], thermal spray pyrolysis [8], and atomic layer deposition [9].

Thermal vacuum evaporation is one of the most used techniques [6-8]. This technique has the advantages of many things, such as easiness, low cost and regular crystal size allocation.

The learning of optical and structural properties of thin films is, considerably, of a large importance for the configuration and investigation of thin films to be utilized as a part of photoelectronic devices. The Cu_2S film is a p-type semiconducting material with cubic crystal structure and a band gap value varies within the range 1.2 eV to 2.5 eV [10-11].

ZnS is a transparent white powder which is formed withina two-phase structure: (α Wurtzite) and (β Zincblende) and is an n-type semiconductor with a wide direct band gap of about (3.2–3.5) eVin the ultra-violet region[12]. It is utilized as a main material for LED and other photoelectronicapplications [13, 14].

The aim of this research it is to examine the influence of copper concentration (x) on the structural and optical properties of $Cu2_{(x)}Zn_{(1-x)}S$ thin films to measure the crystal size,lattice constant and optical constants, such as: absorption coefficient,energy band gap, refractive index, extinction coefficient and dielectric constant.

2. Experiment

 $Cu2_{(x)}Zn_{(1-x)}S$ alloy was formed by weighting appropriate atomic weights of Cu, Zn and S with a high purity of about 99.999% in an evacuated quartz ampoules. The elements weremixed in atomic ratios of copper: (0.0), (0.25), (0.5), (0.75) and (1.0), according to the stoichiometry of $Cu2_{(x)}Zn_{(1-x)}S$. The mixtures were heated firstly, using a furnace from room temperature to (500K) for one hour. Then, the temperature was increased to be about(800 K) for two hours. Sequentially and to ensure homogenousity, the temperature was fixed up to (1100 K) for four hours. The solid ingot was powdered by being grinded to get a $Cu2_{(x)}Zn_{(1-x)}S$ compound.

TheCu2_(x)Zn_(1-x)S compound,having an accurate weight,was placed inside aboatmade of molybdenum (Mo).Cu2_(x)Zn_(1-x)S thin films were grown on square (2.5 x 2.5) cm soda-lime glass substrates bya vacuum thermal evaporation system model (Edward 306A)witha thickness of (500nm)and vacuum pressure of (10⁻⁵)torr. All films were fabricated with a distance between boat and substrate (25 cm)at room temperature.

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Then, the deposition process leaves the systemunder low pressure for an appropriate period in order to get rid of the heat caused by the evaporation processand to ensure that there will be no interaction between air and samples.

The next step was to take out the samples and to put them in the petri dishes so as to be keptaway from external conditions (such as temperature and humidity) for the sake of examining them. The thickness of the deposited films was measuredby using theweighted method.

Structural properties were made by X-ray diffraction device (Philips X-ray Diffractometer), where the specifications of the device are: Target Type (Cu X-ray tube K α), the wavelength of X-rays (0.1541nm); with (40 KV) voltage, (20 mA) current and angles of ($2\theta = 20^{\circ}-90^{\circ}$).

The optical measurements was performed by (UV-Vis) (UV-1800 Spectrophotometer from Shimadzu) within various range of wavelength between (200nm) and (1100nm).

3. Results and Discussion

The study of X-ray diffraction pattern for any material can identify the crystal structure of it. The diffraction pattern of the thin film could be done by determining the peak positions. And that appears in thefalling of the X-ray on surface material with monochromatic wavelength (λ) at an angle (θ), according to (Bragg's law)[15]:

 $2d \sin \theta = n\lambda$

where:

n: integer (1,2,3,).

d: the vertical distance between the two surfaces consecutive.

 λ : wavelength of X-rays.

 $\boldsymbol{\varTheta}$: the incident or reflection X-rays angle.

The thin films were examined within the range between $((20^{\circ}) \text{ and } (60^{\circ}))$ (2 θ) scale angle. To know the value of interplanar spacing (d_{hkl}) , Miller indices (hkl) of cards [American Standard for Testing Materials] (ASTM) can be seen, so as to get the lattice constant (a) of the material by using the equation [15]:

$$\frac{1}{d^2} = \frac{h^2 + k^2 + l^2}{a^2}$$

Figure (1) shows the XRD patterns of $Cu2_{(x)}Zn_{(1-x)}S$ thin films for different concentrations (x) with a thickness of t=500 nm. When x=0.0. There aresix sharp peaks located at: 2θ = (29.15°), (31.72°), (33.15°), (47.41°),(56.52°) and (57.93°) (which correspond to the reflections from (111), (105), (200), (110), (311)and (201) planes respectively of ZnS thin film with cubic phase), while peaks appeared at 2θ = (27.77°), (33.56°), (39.02°), (46.74°)and (54.57°) for composition x=0.25 which correspond to reflections from (111), (107), (102), (110) and (310) planes respectively.

Peaks appeared at 2θ =(28.64°),(38.52°),(40.16°),(47.85°),(54.11°) and (55.95°) for concentration x=0.50 which correspond to reflections from (111), (102), (220), (110), (310) and (311) planes respectively. For composition x=0.75, thepeaks appeare at 2θ =(28.47°),(34.38°),(38.53°),(39.21°), (47.23°),(52.56°), and (55.27°) which correspond to reflections from (111), (200), (102), (220), (110), (310) and (311) planes.

Finally, When x=1.0, therecan be seen six sharp peaks located at 2θ =(27.31°),(37.22°),(37.84°),(45.42°), (51.25°)and (54.26°)which correspond to the reflections from (111), (102), (220), (110), (310) and (311) planes respectively of Cu₂S thin film with cubic phase. These reflections in XRD pattern are, also, in good agreement with the reported values[16,17].



Figure 1: X-ray diffraction pattern for $Cu2_{(x)}Zn_{(1-x)}$ Sthin films with different (x)

There is a shift of 2θ location to lower values and an increase of the peaks intensity and crystalline accompanied the increasing of copper content as given in Table (1).

The X-rays diffraction measurements has shown that the thin films were cubic polycrystalline phase because of the presence of X-ray diffraction peaks in most thin films, as

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illustrated in figure (1). And this is consistent with [18,19]. It also, calculated the size of the crystal grains (crystal size *G*) for each of the Bragg's peaks of all samples using Scherrer formula [20]:

B: Full Width at Half Maximum (FWHM). λ : Wavelength of X-rays used (λ = 0.15418nm). θ_{B} : is the Bragg's angle.

$$G = \frac{K\lambda}{B\cos\theta_B}$$

K = 0.89 is the shape factor

Table 1: X-ray diffraction data for thin $Cu2_{(x)}Zn_{(1-x)}S$ films with different concentrations (x)

v	d _(exp.)	d _(stand.)	$2\theta_{(exp.)}$	$2\theta_{(\text{stand.})}$	հել	EWHM	Lattice	G _(aye.)
Λ	(A)	(A)	(deg.)	(deg.)	пкі	T, AA LIIVI	constant (A^0)	(A^0)
(0.0) ZnS	3.067	3.130	29.15	28.55	(111)	0.541		
	2.820	2.759	31.72	32.41	(105)	0.473		
	2.701	2.711	33.15	33.08	(200)	0.522		
	1.915	1.910	47.41	47.54	(110)	0.611	5 312	253.26
	1.423	1.634	56.52	56.28	(311)	0.755	5.512	235.20
	1.590	1.601	57.93	57.59	(201)	0.874		
(0.25) Cu2 _(0.25) Zn _(0.75) S	3.104		28.77		(111)	0.429		
	2.673		33.56		(107)	0.433		
	2.312		39.02		(102)	0.565		
	1.944		46.74		(110)	0.259	5.376	338.42
	1.681		54.57		(310)	0.282		
0.50 Cu2 _(0.50) Zn _(0.50) S	3.117		28.64		(111)	0.342		
	2.340		38.52		(102)	0.476		
	2.244		40.16		(220)	0.198		
	1.901		47.85		(110)	0.397	5 208	219 75
	1.696		54.11		(310)	0.385	5.598	546.75
	1.641		55.95		(311)	0.502		
0.75 Cu2 _(0.75) Zn _(0.25) S	3.142		28.47		(111)	0.276		
	2.610		34.38		(200)	0.315		
	2.340		38.53		(102)	0.485		
	2.298		39.21		(220)	0.358		
	1.925		47.23		(110)	0.246	5.442	270.25
	1.742		52.56		(310)	1.534		219.33
	1.663		55.27		(311)	0.472		
	3.274	3.290	27.31	27.17	(111)	1.104		
	2.414	2.436	37.22	36.95	(102)	0.374		
1.0	2.383	2.406	37.84	37.38	(220)	0.318		
Cu ₂ S	2.003	2.031	45.42	44.57	(110)	0.229	5 670	217 12
	1.782	1.753	51.25	52.18	(310)	0.267	3.070	31/.12
	1.688	1.703	54.26	53.84	(311)	0.283		

The average crystal size has beenshowed to be in the range of (253) A⁰ to (348) A⁰as given in table (1) .The increaseand decreasein particle size with copper concentration (x) may have beenbecause of the increase in long-range arrangement crystalline or could be subscribed to other factors during the preparation of thinfilms.

The increase in particle size might be because of the agglomeration that happened between smallgrainsorit might be because of the potential energy difference between the various size of particles. This can, likewisely, happen through the diffusion process.

On the other hand, the optical properties have been made by checking the transmittance spectra of thin films prepared by using the type of spectrophotometer (UV-Vis Double Beam Spectrophotometer).

The transmittance of the thin films (T) was measured within a wavelength range between (200nm) and (1100nm).The absorption spectrum of the (ZnS) thin film is within the spectrum UV region and the absorption spectrum of the (Cu_2S) thin film is within the spectrum visible region, as shown in Fig.(2).



Figure 2: Transmittance (T) versus wavelength (λ) for thin Cu2_(x)Zn_(1-x)S films with different concentrations (x)

Moreover, the absorbance (A) in terms of transmittance can be calculated by applying the following relationship, as shown in Fig.(2)[21]:

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$$A = \log -\frac{1}{2}$$



Figure 3: Absorbance (A) versus wavelength (λ) for thin $Cu2_{(x)}Zn_{(1-x)}S$ films with different concentrations (x)

With respect to the absorption of coefficient (α), it can be calculated by the following relationship [21]:

$$\alpha = 2.303 \frac{A}{t}$$

Where *t* is the thickness of sample

The value of the absorption coefficient changes with the wavelength (where this change depends on the properties of semiconductor material as well as on energy photons (hv)), the value of the optical energy gap (Eg) of the thin film canbe known by having the value of (α)



Figure 4: Absorption coefficient (α) versus wavelength (λ) for thin Cu2_(x)Zn_(1-x)S films with different concentrations (x)

By plotting the relationship between (α) and (λ), it can be noticed that the absorption coefficient in the absorption region of high values is larger than (10⁴) cm⁻¹, as shown in Fig.(4). And this means that the charge carriers move from the extended levels in the valence band to the extended levels in the conduction band thereby, generating pair electron-hole in a process called as: the fundamental absorption process.

This value of the absorption coefficient shows that the electronic transition of semiconductor is of a direct transition. And this is a general property for compounds Group (II - VI) and especially compound (ZnS) and Cu_2S .

Besides, the possible value of the energy gap calculation is based on the nature of the electronic transitions between energy bands[22]:

$$\alpha(h\nu) = A_i (h\nu - E_g)^n$$

Where A_i is constant and n= 1/2 is for allowed direct transition.

Practically, it is possible to calculate the energy value by plotting the relationship between the photon energy (hv) as a function of $(\alpha hv)^2$ and the extrapolation (i.e. E_g) of the portion at $[(\alpha hv)^2 = 0]$, as shown in Fig.(5). The value of the optical energy gap decreases with the increasing of copper content (x) for all samples, as shown in Table (2)

The absorption coefficient has small values at low energy of all thin films. But its valueincreases in the absorption edge, as illustrated in the figure (4) where it is clearly noticed that the increase in the proportion of copper has led to the deviation of the edge of the optical absorption towards the low energies. And that is because of the presence of defects in crystal structure, or the so-called trap states inside the optical energy gap [21] . This deviation has led to a reduction of the optical energy gap.



Figure 5: $(\alpha h\nu)^2$ versus hv for thin $Cu2_{(x)}Zn_{(1-x)}S$ films with different concentrations (x)

It can be concluded that the increase in copper ratio has brought about a significant change in the value of the optical energy gap (E_g) which indicates that it may cause rise to some of the structural defects that appear in tails in the region between the valence and conduction band.

with different concentrations (x)				
Х	$E_g(eV)$			
(0.0) ZnS	3.1			
(0.25) Cu2 _(0.25) Zn _(0.75) S	2.85			
0.50 Cu2 _(0.50) Zn _(0.50) S	2.65			
0.75 Cu2 _(0.75) Zn _(0.25) S	2.35			
1.0 Cu ₂ S	2.08			

Table 2: Optical energy gap (Eg) for thin Cu2(x)Zn(1-x)S filmswith different concentrations (x)

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The extinction coefficient has been calculated from the equation[23]:

$$k = \frac{\alpha \lambda}{4 \pi}$$

Drawing the relationship between the extinction coefficient as afunction of wavelengthfor all thin films, the value of extinction coefficient decreases with increasing wavelength is observed, as shown in Fig.(6).



Figure 6: The extinction coefficient (k) versus wavelength (λ) for thin Cu2_(x)Zn_(1-x)S films with different concentrations (x)

The values of high extinction coefficient at short wavelengths can be traced back to the loss of photon energy as a result of the fundamental absorption process where the growing influence of extinction coefficient is correlated with the increasing of the copper ratio for all films.

The refractive index (n) can be calculated from the following equation [24].

$$\mathbf{n} = \left[\frac{4R}{(R-1)^2} - \mathbf{k}^2\right]^{\frac{1}{2}} - \frac{(R+1)}{(R-1)}$$

where R is a reflecttance



Figure 7: The refractive index (n) versus wavelength (λ) for thin Cu2_(x)Zn_(1-x)S films with different concentrations (x)

This figure shows that the refractive indexin general increases, then decreases with the increasing of copper content to prepared films, as shown in Fig.(7). The behaviour of the refractive index with various concentrations of the copper impurity is comparatively autonomous.

The real and imaginary part of the dielectric constant (ε_r and ε_i) can be calculated by using the equations[25]: $\varepsilon_r = n^2 - k^2$

$$\epsilon_{i} = 2nk$$

Variation of dielectric constants (ε_r) and (ε_i) with wavelength for different concentrations is shown in figures.(8,9). From these figures, it can be shown obviously that the values of dielectric constants initially increases with the increase of wavelength and reaches a maximum value and then decreases with the increase of wavelength as the same fashion of refractive index.



Figure 8: The real part of the dielectric constant (ϵ_r) versus wavelength (λ) for thin $Cu2_{(x)}Zn_{(1-x)}S$ films with different concentrations (x)



Figure 9: The imaginary part of the dielectric constant (ϵ_i) versus wavelength (λ) for thin $Cu2_{(x)}Zn_{(1-x)}S$ films with different concentrations (x)

4. Conclusions

The main purpose of this research is to study the effect of copper concentration on the structural and optical properties of $Cu2_{(x)}Zn_{(1-x)}S$ thin films. So, the thin films have been prepared with ratios of Cu x= (0.0), (0.25), (0.50), (0.75) and (1.0) by heating the mixture of Cu, Zn and S elements in order to prepare the alloys. The thin films have been prepared by vacuum thermal evaporation methodwith a thickness of (500) nm at room temperature.

Volume 5 Issue 11, November 2016 <u>www.ijsr.net</u> Licensed Under Creative Commons Attribution CC BY X-ray diffraction technique (XRD) results have shown that the thin films of $Cu2_{(x)}Zn_{(1-x)}S$ are polycrystalline structure with cubic phase. The optical measurements have showed that the $Cu2_{(x)}Zn_{(1-x)}S$ thin films have direct energy gap which decreases with the increasing of copper concentration.

As calculating absorption coefficients (α), extinction coefficients (k)and refractive index (n), it has also found that it decreases with the increasing of concentration (x). It was noticed that the edge of the optical absorption shifted towards short wavelength.

For the dielectric constant (ε) , it is observed that the value of (ε) initially increases with the increasing of wavelength and reaches its maximum value and then decreases, as in the same fashion of refractive index.

References

- [1] G. I. Yepifanov, Yu. A. Moma, "Introduction to Solid State Electronics", Publishers, Moscow, (1984).
- [2] C. Kittle, "Introduction to Solid State Physics", 5th edition, John Wiley and Sons, Inc., Canada, (1976).
- [3] D. Gerig, "Electrons in Metals of Semiconductor", McGraw – Hall, Landon, (1969).
- [4] Jacques Vedel, Pierre Cowache and Micheal Soubeyranel *Solar Energy Materials*, 10 ,p.(25-34), (1984).
- [5] S. Schneider, J.R. Ireland, M.C. Hersam, T.J. Marks, Chem. Mater. 19 ,p.2780,(2007).
- [6] S.V. Bagul, S.D. Chavhan, R. Sharma, J. Phys. Chem. Solids 68, p. 1623, (2007).
- [7] Couve, S., Gouskov, L., Szepessy, L., Vedel, J., and Castel, E, "Resistivity and Optical Transmission of CuXS Layers as a Function of Composition", Thin Solid Films ,15,p.(223-231), (1973).
- [8] Wang, S. Y., Wand, W. and Lu, Z. H., "Asynchronous

 Pulse Ultrasonic Spray Pyrolysis Deposition of CuxS(X=1,2) Thin Films", Mater. Sci. Eng., B, 103, p.(84-188), (2003).
- [9] Elijah Thimsen, Qing Peng, Alex B. F. Martinson, Michael J. Pellin, Jeffrey W. Elam Chem. Mater, 23, p.(4411–4413),(2011).
- [10] M.S Shinde, P.B Ahirrao, I.J Patil and RS Patil, Indian Joural of Pure and Applied Physics, vol. 50, sep,p. 657-660,(2012).
- [11] S.V. Bagul, S.D. Chavhan and R. Sharma, J. Phys.Chem, solids, 68, p.1623-1629,(2007).
- [12] J. Mu and Y. Zhang ,Appl. Surf. Sci. 252 . p.7826,(2006).
- [13] K. Skwok and X. Sun,"Thin Solid Films", Vol. 335, p. 229,(1998).
- [14] A. Antony, K.V. Mirali, R. Manoj, M. K.Jayaraj, Mater.Chem.Phys, Vol. 90, p. 106,(2005).
- [15] H. P. Klug and L. E. Alexander. X-ray diffraction procedure. John Wiley & Sons, New York, USA (1974).
- [16] H. K. Sadekar, N. G. Deshpande, Y. G. Gudage, A. Ghosh, S. D. Chavhan, S. R. Gosavi and R. Sharma, J. Alloy and Compounds, 453, 519 (2008).
- [17] M.S Shinde, P.B.Ahirrao, I.J.Patil , R.S.Patil " thickness dependent electrical and optical properties of

nanocrystalline copper sulphide thin films grown by simple chemical route" Vol.50,pp(657-660),(2012).

- [18] M. Oikkonen, M. Blomberg and T. Tuomi, M. Tammenmaa, "X-ray Diffraction Study of Microstructure in ZnS Thin films grown From Zinc Acetate by Atomic Layer Epitaxy", Thin Solid Films, Vol. (124), pp. (317-321), (1985).
- [19] A. Yoshikawa, S. Yamaga, K. Tanaka and H. Kasai, "Growth of Low-Resistively High-Quality ZnSe, ZnS films by Low-Pressure Metaloganic Chemical Vapour Deposition", J. of Cry. Growth. Vol. (72). pp. (13-16), (1985).
- [20] B.D. Culitty, " Elements of X-ray Diffraction", 2nd edition, (1977).
- [21] David. L. Greenaway and Gunther Harbeke, "Optical Properties and Band Structure of Semiconductors", Pergamon Press, Oxford (1970).
- [22] Steven S. Hegedus and William N. Shafarman. Thinfilm solar cells: Device measurement and analysis. Progress in Photovoltaics: Research and Application, 12:p.155–176, (2004).
- [23] I. V. Pankove, Optical Processes in Semiconductors, Dover Inc., New York, (1975).
- [24] J.Millman "Microelectronics" Murray Hill, Book Company Kogakusha, Vol. 642, p.172. (1979).
- [25] I. V. Pankove, Optical Processes in Semiconductors, Dover Inc., New York, (1975).

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